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Metryx' Mentor Wins Semiconductor International's Editor's Choice Best Product Award 2007

BRISTOL, UK—July 2, 2007—Metryx, Limited, a supplier of mass metrology equipment to the semiconductor manufacturing industry, today announced that it received the coveted Editor's Choice Award for 2007 from leading industry magazine *Semiconductor International*. The award was given in recognition of Metryx' Mentor mass metrology technology in a year that has seen Metryx revenues double based on growing acceptance on the company's technology in the global semiconductor manufacturing industry. The award will be officially presented to Metryx on July 18th at an event during SEMICON West 2007, in San Francisco.

The *Semiconductor International* award marks the second distinguished award received by the company this year, having already been presented with the Queen's Award for Enterprise, one of the most prestigious awards to be given in UK enterprise.

"A lot of people have put a great deal of effort into making this technology and this company a success. To receive awards such as these is great recognition for those efforts," stated Adrian Kiermasz, president and CEO of Metryx, Ltd. "To succeed in this industry you need to offer a significant benefit in order to be adopted. We have always believed that our technology does just that and appreciate being recognized for what we bring to the industry."

Metryx' Mentor technology offers a unique measurement technology known as mass metrology. This approach utilizes innovative mass measurement technology, meaning it uses a series of very accurate force measurements and the mass change encountered during the process is measured to atomic level accuracy. The mass change is a direct consequence of the process change. Every process has a window of operation and hence a normal distribution of operation (± 3 sigma). The mass change has a corresponding normal distribution (± 3 sigma) that exactly correlates to the process. Should the process mean drift, or the process go outside its normal distribution, the mass change will also shift and the process can be corrected or stopped immediately saving scrap or preventing yield loss.

Mass metrology is used on actual product wafers as there absolutely is no front side intervention or intrusion, and in many cases measurement accuracies can be achieved to the sub-Ångström level. Mass change caused by process change correlates directly. Mass change represents the whole process, so that if anything changes in the process, mass change variation will pick it up and immediately provide information that the process is out of specification. Mass metrology is applicable to deposition, etch, and CMP

processes, in fact, any device manufacturing process which involves a measurable mass change can be monitored and assessed using Mass metrology. It can also be used on dielectric and metal layers. Ultimately, the technology can reduce the use of test wafers, improve cycle time and increase yield.

About Metryx

Metryx is a semiconductor equipment manufacturer specializing in unique nanotechnology mass measurement techniques. Based in Bristol, England, Metryx' non-destructive 200mm and 300mm metrology tools offer atomic layer accuracy making them ideal for material characterization and device manufacture process control. For more information on the company and its products please visit www.metryx.net